

Notice of References Cited				Application No. 09/437,135		Applicant(s) Yamazaki et al.	
				Examiner Erik Kielin		Group Art Unit 2813	

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* A copy of this reference is not being furnished with this Office action.
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FORM PTO-892 (REV. 2-92)				U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE				SERIAL NO. <div style="border: 1px solid black; padding: 2px;">08111522</div>		GROUP ART UNIT <div style="border: 1px solid black; padding: 2px;">1104</div>		ATTACHMENT TO PAPER NUMBER <div style="border: 1px solid black; padding: 2px;">11</div>	
NOTICE OF REFERENCES CITED								APPLICANT(S) <div style="border: 1px solid black; padding: 2px;">YAMAZAKI et al</div>					
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